Dow Corning Announces New CVD Products

10.07.2002 - MIDLAND, Mich., July 8, 2002 - Dow Corning Corporation today announced the introduction of three new chemical vapor deposition (CVD) precursors -- Z4MS(TM), ZTOMCATS(TM) and Z2DM(TM). Dow Corning's introduction of these products demonstrates a continued effort to innovate solutions that meet the changing demands of the dielectric market, and enables a wide range of choices to the semiconductor industry.

The new products -- Dow Corning(R) Z2DM CVD Precursor (dimethyldimethoxysilane), Dow Corning(R) Z4MS CVD Precursor (tetramethylsilane), and Dow Corning(R) ZTOMCATS CVD Precursor (tetramethycyclotetrasiloxane) -- are multifunctional silicon source liquids specifically designed for advanced PECVD processes used to deposit thin film dielectrics including, passivation, etch stop, hard mask and copper diffusion barrier films. These high performance liquid precursors are compatible with copper dual damascene and aluminum processes.

Additionally, Dow Corning has the manufacturing capacity and site redundancy required to meet any and all of its customers' needs across the globe. The company's global presence enables it to provide customers with local technical service and a stable supply of quality product.

Schumacher -- a business unit of Air Products and Chemicals, Inc. and a leading worldwide supplier of ultra-high purity chemicals and delivery equipment to the global electronics industry -- has agreed to be the master distributor of the new products. This agreement represents a strong alliance between two of the largest players in the liquid CVD precursor market and will enable the companies to serve any customer in any location in the world. Schumacher will package Dow Corning's precursors and will sell to end user customers and distributors through its worldwide distribution network.